

DEVICE FOR TREATING GAS POLLUTANTS

Abstract

A device for treating gas pollutants, comprises an air inlet part, a first treatment unit, a second treatment unit, and a non-mechanical drainage device, wherein the air inlet part comprises an air inlet chamber and at least one guiding pipeline; the guiding pipeline is connected to the air inlet chamber and guides an effluent from a semiconductor fabrication process to the air inlet chamber; the first treatment unit is coupled below the air inlet part and used to weaken the effluent; the non-mechanical drainage device is coupled to the first treatment unit; the drainage device is used to guide the effluent to move towards an opening; and the second treatment unit is coupled to the drainage device by means of the opening, receives the effluent from the first treatment unit, and further weakens the effluent.

FIG. 2B